## WEST

## **Freeform Search**

Database	US Patents Full-Text Database US Pre-Grant Publication Full-Text Database JPO Abstracts Database EPO Abstracts Database Derwent World Patents Index IBM Technical Disclosure Bulletins
Term: Display: Generate	L3 and @pd<20000927  25 Documents in Display Format: - Starting with Number 1  O Hit List • Hit Count O Side by Side O Image
	Search Clear Help Logout Interrupt  Main Menu Show S Numbers Edit S Numbers Preferences Cases
	Search History

DATE: Thursday, January 30, 2003 Printable Copy Create Case

Set Name side by side	Set Name Query ide by side		Set Name
DB=US	SPT,PGPB; PLUR=YES; OP=ADJ	result set	
<u>L5</u>	5403438[uref]	1	L5
<u>L4</u>	L3 and @pd<20000927	163	<u>20</u> L4
<u>L3</u>	L2 and ((coat\$3 or cover\$3) near5 resist)	287	<u></u> L3
<u>L2</u>	L1 same (pattern\$3 near5 first resist)	434	<u></u> L2
<u>L1</u>	resist same pattern\$3	36779	<u>L1</u>

END OF SEARCH HISTORY

L Number				
'	379	3 (resist near pattern) same cover\$3	DB	Time stamp
	1.	, , , , , , , , , , , , , , , , , , , ,	USPAT;	2003/01/30 15:3
			US-PGPUB	;
	1		EPO; JPO;	
•	l		DERWENT	:
2	194	((resist near pattern) same cover\$3) same (second near resist)	IBM_TDB	
			USPAT;	2003/01/30 15:39
	1		US-PGPUB	:
			EPO; JPO;	
			DERWENT	
3	130	(((resist near nattern) same accords)	IBM_TDB	
		(((resist near pattern) same cover\$3) same (second near resist)) and @pd<20000927	USPAT;	2003/01/30 15:42
		100.00) and @pu-20000927	US-PGPUB;	2003/01/30 15:42
			EPO; JPO;	
			DERWENT;	
.	105769 resist same (pattern\$3 or etch\$3)	IBM_TDB		
		resist same (pattern\$3 or etch\$3)	USPAT;	2000/04/05
1			US-PGPUB;	2003/01/30 15:36
			EPO; JPO;	
			DERWENT;	
	2698	(regist a /	IPM TOD	1
ŀ	2090	(resist same (pattern\$3 or etch\$3)) same (second near resist)	IBM_TDB	
		(**************************************		2003/01/30 12:03
			US-PGPUB;	
			EPO; JPO;	
	000		DERWENT;	
	933 ((resist same (pattern\$3 or etch\$;	((resist same (pattern\$3 or etch\$3)) same (second near	IBM_TDB	1
ł		resist)) same (coat\$3 or cover\$3)	USPAT;	2003/01/30 13:06
		US-PGPUB;		
1			EPO; JPO;	
j			DERWENT;	
r	645	(((resist same (pattern\$3 or etch\$3)) same (second near resist)) same (coat\$3 or expension)	IBM_TDB	
j	r	resist)) same (coat\$3 or cover\$3)) and @pd<20000927	USPAT;	2003/01/30 13:11
1	- 1	and @pu<20000927	US-PGPUB;	
	ŀ		EPO; JPO;	
1			DERWENT;	1
}	15	((((resist same (pattern\$3 or etch\$3))) same (second near	IBM_TDB	
			USPAT;	2003/01/30 12:09
	1	((polysilesesquioxane or "SOG") same etch\$3)	US-PGPUB;	2 30 12.03
	1	s so so / same etchas)	EPO; JPO;	
ł			DERWENT:	
	193	((resist) same (reat\$3 or etch\$3)) same (second near	IBM TDB	
			USPAT:	2003/01/30 13:08
	10	or "SOG" or metal))	US-PGPUB;	30/0 //3/08
1	1		EPO; JPO;	1
			DERWENT:	ŀ
	133 (	((resist same (pattern\$3 or otab@a))	IBM_TDB	
	l r	((resist same (pattern\$3 or etch\$3)) same (second near		2003/01/30 13:12
			US-PGPUB:	2003/01/30 13:12
		or "SOG" or metal))) and @pd<20000927	EPO; JPO;	
	-		DERWENT:	1
			IBM_TDB	